_		2006.07
Q		2006-07-
12	Of Fizo same plasma same	06 13:20:41
	(photoresist or resist or	13:20:41
	photosensitive near5 remov\$3 or	1
	residue or (by-product))	
١,	3776UPGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD((hydrogen or h2) near10 (water	2006-07-
15	or H2O)) same (plasma)	06
ı		13:20:29
١.	3775 UPGPB, USPT, USOC, EPAB, JPAB, DWPI, TDBD (hydrogen or h2) near 10 (water	2006-07-
i.	or H2O)	06
ı	J. 1.2-5)	13:20:15
١	TORD bydrogen and water	2006-07-
1	3774UPGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD hydrogen and water	06
		13:19:15
l		2006-07-
1	33773 UPGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD (photoresist or resist or photosensitive) near5 (remov\$3	
1	or residue or (by-product))	13:18:07
I	or residue or (by-product)	2006-07-
۱	83772 UPGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD (plasma) and (remov\$3 or	06
ı	residue or (by-product))	13:17:48
I		2006-07-
I	S3771 UPGPB, USPT, USOC, EPAB, JPAB, DWPI, TDBD (remov\$3 or residue or (by-	06
ı	product)) sinae (piasina same	13:17:27
I	remov\$3 or residue or (by-	15:17:27
I	product) same photoresist or	
ı	resist or photosensitive)	
ı	S3770 UPGPB, USPT, USOC, EPAB, JPAB, DWPI, TDBD (hydrogen or h2) and (water or	2006-07-
ı	H2O)	06
۱		13:16:40
١	S3769 UPGPB, USPT, USOC, EPAB, JPAB, DWPI, TDBD (plasma) same (remov\$3 or	2006-07-
١	residue of (by-product) / same	06
١	(photoresist or resist or	13:15:57
١	photosensitive)	
1		2006-07-
1	S3768 UPGPB, USPT, USOC, EPAB, JPAB, DWPI, TDBD plasma	06
		13:15:42
1	TOPD remov\$3 or residue or (by-	2006-07-
	S3767UPGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD remov\$3 or residue or (by-product)	06
1	product)	13:14:55
	TO THE PROPERTY OF THE PROPERTY OF POSIST OF	
	S3766UPGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD photoresist or resist or photosensitive	
	pnotosenstive	